

## PALM INTRANET

Day: Friday Date: 11/21/2003 Time: 08:52:39

## **Inventor Name Search Result**

Your Search was:

Last Name = DOPPER First Name = GEBHARD

Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
10085527	Not Issued	071		METHOD AND DEVICE FOR TREATING THE SURFACE OF A PART	DOPPER, GEBHARD
10045770	6602542	150	01/10/2002	DEVICE FOR CLEANING AN ARTICLE	DOPPER, GEBHARD
<u>09840556</u>	6382920	150		ARTICLE WITH THERMAL BARRIER COATING AND METHOD OF PRODUCING A THERMAL BARRIER COATING	DOPPER, GEBHARD
09840552	Not Issued	071		PROCESS FOR CLEANING AN ARTICLE, PROCESS FOR COATING AN ARTICLE, AND DEVICE THEREFOR	DOPPER, GEBHARD

Inventor Search Completed: No Records to Display.

Search Another: Inventor	Last Name	First Name	
Search Another: Inventor	DOPPER	GEBHARD	Search

To go back use Back button on your browser toolbar.

Back to PALM | ASSIGNMENT | OASIS | Home page

L Number	Hits	Search Text	DB	Time stamp
1	1	6602542.pn.or6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:55
2	2	6602542.pn. or 6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:57
3	0	427/532,533,534,535	USPAT; US-PGPUB	2003/11/21 08:58
4	1077	(427/532,533,534,535).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
5	280	(427/551).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
6	746	(427/596,597).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
7	919	(427/255.11,255.19,255.21,255.5).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
8	734	(427/318,319).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
9	2014	(216/63,64,67,74,75).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
10	1291	(204/192.32,192.35,298.31,298.34).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
11	6535	((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)	USPAT; US-PGPUB	2003/11/21 08:59
12	3	((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/21 09:02
13	9	(clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:11
14	7	discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (((427/532,533,534,535).CCLS.) ((427/5551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:02
15	2	((204/192.32,192.35,298.31,298.34).CCLS.))) not ((clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (Dopper.in. or Siemens.as.))	USPAT; US-PGPUB	2003/11/21 09:05
16	49	discharge)) near3 clean\$3))	USPAT; US-PGPUB	2003/11/21 09:09

17	47	(((electron near5 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near5 clean\$3))) not	USPAT; US-PGPUB	2003/11/21 09:05
		((((427/532,533,534,535).CCLs.)		
1		((427/551).CCLS.) ((427/596,597).CCLS.)		
		((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)		
		((216/63,64,67,74,75).CCLS.)		
		((204/192.32,192.35,298.31,298.34).CCLS.))		
		and ((electron near3 heat\$3) same ((plasma		
		or ion or sputter\$3 or (glow adj discharge)) near3 clean\$3)))		
18	21	((electron near5 heat\$3) same ((plasma or	EPO; JPO;	2003/11/21 09:09
		ion or sputter\$3 or (glow adj discharge))	DERWENT; IBM TDB	
19	100	near5 clean\$3)) (clean\$3 near5 (plasma or (glow adj	USPAT;	2003/11/21 09:26
		discharge) or sputter\$3 or ion)) and	US-PGPUB;	
		(electron with (flow\$3 or flux\$3) with	EPO; JPO; DERWENT;	
		(control\$5 or switch\$3))	IBM TDB	
20	91	((clean\$3 near5 (plasma or (glow adj	USPĀT;	2003/11/21 09:15
		discharge) or sputter\$3 or ion)) and	US-PGPUB;	
		(electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) ) not ((clean\$3	EPO; JPO; DERWENT;	
1		near5 (plasma or (glow adj discharge) or	IBM_TDB	
		sputter\$3 or ion)) and (electron with		
1		(flow\$3 or flux\$3) with (control\$5 or switch\$3)) and		
		(((427/532,533,534,535).CCLS.)		
		((427/551).CCLS.) ((427/596,597).CCLS.)		
		((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)		
		((216/63,64,67,74,75).CCLS.)		
		((204/192.32,192.35,298.31,298.34).CCLs.)))		
21	137	(((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.)	USPAT; US-PGPUB;	2003/11/21 09:16
		((427/255.11,255.19,255.21,255.5).CCLS.)	EPO; JPO;	
		((427/318,319).CCLS.)) and	DERWENT;	
		(((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	IBM_TDB	
22	6	(((427/532,533,534,535).CCLS.)	USPAT;	2003/11/21 09:20
		((427/551).CCLS.) ((427/596,597).CCLS.)	US-PGPUB	
		((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)		
		((216/63,64,67,74,75).CCLS.)		
		((204/192.32,192.35,298.31,298.34).CCLS.))		
		and ((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or		-
		(positiv\$3 near2 bias)) with (((sputter\$3		
		or plasma or (glow adj discharge) or ion)		
		near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))		
23	259	((alternat\$4 or switch\$3) with ((electron	USPAT;	2003/11/21 09:21
		near2 (heat\$3 or bombard\$5)) or (positiv\$3	US-PGPUB;	
		near2 bias)) with (((sputter\$3 or plasma	EPO; JPO; DERWENT;	
		or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4	IBM TDB	
		near2 bias)))	_	
24	59	(((alternat\$4 or switch\$3) with ((electron	USPAT;	2003/11/21 09:28
		near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma	US-PGPUB; EPO; JPO;	
		or (glow adj discharge) or ion) near2	DERWENT;	
		(clean\$3 or bombard\$5)) or (negativ\$4	IBM_TDB	
		near2 bias)))) and ((coat\$3 or \$4CVD or deposit\$3) near5 (substrate or base or		
		metal\$4 or turbine or structure or body or		
0.5	^^-	basebody))	rac Dam :	2002/11/21 00:27
25	207	(electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5)	USPAT; US-PGPUB;	2003/11/21 09:27
		with (switch\$3 or alternat\$5 or (open\$3	EPO; JPO;	
		near3 clos\$3)))	DERWENT;	
		<u> </u>	IBM TDB	<u> </u>

		61 62	HCDAM.	2003/11/21 09:28
26	223	(electron with (flow\$3 or flux\$3 or	USPAT; US-PGPUB;	2003/11/21 09:28
		outflow\$3 or outflux\$3) with (control\$5 or	EPO; JPO;	
		regulat\$3 or adjust\$3) with (switch\$3 or	DERWENT;	
i		alternat\$5 or (open\$3 near3 clos\$3)))	IBM TDB	
	_			2003/11/21 09:28
27	3	( (electron with (flow\$3 or flux\$3 or	USPAT;	2003/11/21 09:28
	i	outflow\$3 or outflux\$3) with (control\$5 or	US-PGPUB;	
		regulat\$3 or adjust\$3) with (switch\$3 or	EPO; JPO;	
ļ		alternat\$5 or (open\$3 near3 clos\$3))) )	DERWENT;	
1		and (((427/532,533,534,535).CCLS.)	IBM_TDB	
	1	((427/551).CCLS.) ((427/596,597).CCLS.)		
	1	((427/255.11,255.19,255.21,255.5).CCLS.)		
		((427/318,319).CCLS.)		
		((216/63,64,67,74,75).CCLS.)		1
		((204/192.32,192.35,298.31,298.34).CCLS.))		
28	71		USPAT;	2003/11/21 09:28
		outflow\$3 or outflux\$3) with (control\$5 or	US-PGPUB;	
	1	regulat\$3 or adjust\$3) with (switch\$3 or	EPO; JPO;	!
		alternat\$5 or (open\$3 near3 clos\$3))) )	DERWENT;	
		and ((coat\$3 or \$4CVD or deposit\$3) near5	IBM_TDB	
		(substrate or base or metal\$4 or turbine		
		or structure or body or basebody))		
29	65	(( (electron with (flow\$3 or flux\$3 or	USPAT;	2003/11/21 09:29
		outflow\$3 or outflux\$3) with (control\$5 or	US-PGPUB;	
		regulat\$3 or adjust\$3) with (switch\$3 or	EPO; JPO;	
		alternat\$5 or (open\$3 near3 clos\$3))) )	DERWENT;	
		and ((coat\$3 or \$4CVD or deposit\$3) near5	IBM_TDB	
		(substrate or base or metal\$4 or turbine		
		or structure or body or basebody))) not		
ł		((( (electron with (flow\$3 or flux\$3 or	}	
		outflow\$3 or outflux\$3) with (control\$5 or		
1		regulat\$3 or adjust\$3) with (switch\$3 or		
		alternat\$5 or (open\$3 near3 clos\$3))) )		
ĺ		and (((427/532,533,534,535).CCLS.)		
		((427/551).CCLS.) ((427/596,597).CCLS.)		
		((427/255.11,255.19,255.21,255.5).CCLS.)		ļ
		((427/318,319).CCLS.)		
	İ	((216/63,64,67,74,75).CCLS.)		
	į	((204/192.32,192.35,298.31,298.34).CCLS.)))		
1		or ((((alternat\$4 or switch\$3) with		
1		((electron near2 (heat\$3 or bombard\$5)) or		
		(positiv\$3 near2 bias)) with (((sputter\$3		
1		or plasma or (glow adj discharge) or ion)	1	
		near2 (clean\$3 or bombard\$5)) or		
		(negativ\$4 near2 bias)))) and ((coat\$3 or	ĺ	
		\$4CVD or deposit\$3) near5 (substrate or	1	
		base or metal\$4 or turbine or structure or		
1		body or basebody))))		
1	1	1 2001 01 2000001, , , ,	1	1